

(19) World Intellectual Property Organization  
International Bureau



(43) International Publication Date  
15 February 2001 (15.02.2001)

PCT

(10) International Publication Number  
**WO 01/11426 A1**

(51) International Patent Classification<sup>7</sup>:  
7/16, H05K 3/12, B41M 3/00

G03F 1/00,

(74) Agents: COZENS, Paul, Dennis et al.; Mathys & Squire,  
100 Gray's Inn Road, London WC1X 8AL (GB).

(21) International Application Number: PCT/GB00/02077

(22) International Filing Date: 30 May 2000 (30.05.2000)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:

9912437.2 27 May 1999 (27.05.1999) GB  
0005929.5 10 March 2000 (10.03.2000) GB

(71) Applicant (for all designated States except US): PAT-  
TERNING TECHNOLOGIES LIMITED [GB/GB];  
Unit 7, The Maltings, Green Drift, Royston, Hertfordshire  
SG8 5DY (GB).

(72) Inventor; and

(75) Inventor/Applicant (for US only): SPEAKMAN, Stuart  
[GB/GB]; 7 Chapel Drive, Little Waltham, Chelmsford, Es-  
sex CM3 3LW (GB).

(81) Designated States (national): AE, AG, AL, AM, AT, AU,  
AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE,  
DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU,  
ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS,  
LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO,  
NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR,  
TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.

(84) Designated States (regional): ARIPO patent (GH, GM,  
KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian  
patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European  
patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE,  
IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG,  
CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).

Published:

- With international search report.
- With amended claims and statement.

For two-letter codes and other abbreviations, refer to the "Guid-  
ance Notes on Codes and Abbreviations" appearing at the begin-  
ning of each regular issue of the PCT Gazette.

(54) Title: METHOD OF FORMING A MASKING PATTERN ON A SURFACE

(57) Abstract: A method of forming a masking pattern on a surface using the technique of droplet ejection to deposit droplets of deposition material, said method comprising depositing a plurality of droplets on said surface to form such a pattern comprising multiple discrete or coalesced extended portions.

WO 01/11426 A1